Phosphoric Acid, 85% CMOS

(orthophosphoric acid)





Material No.: 0264-05 Batch No.: 0000000529

Manufactured Date: 2012/04/23

## Certificate of Analysis

Test	S pecification	Result
Assay (H <sub>3</sub> PO <sub>4</sub> ) (by acidimetry)	85.0 -87.0 %	86.6
Color (APHA)	<= 10	5
Color after Heating	Passes Test	PT
S pecific Gravity at 60°/60°F	1.691 -1.710	1.701
Reducing S ubstances	Passes Test	PT
Volatile Acids (µeq/g)	<= 0.16	0.16
Chloride (CI)	<= 1 ppm	<1
Nitrate (NO <sub>3</sub> )	<= 2 ppm	<2
Sulfate (SO <sub>4</sub> )	<= 12 ppm	<4
Trace Impurities -Aluminum (Al)	<= 0.5 ppm	< 0.0
Frace Impurities –Antimony (Sb)	<= 10 ppm	< 0
Trace Impurities -Arsenic (As)	<= 0.05 ppm	< 0.03
Trace Impurities -Calcium (Ca)	<= 1.5 ppm	< 0.2
Trace Impurities -Chromium (Cr)	<= 0.2 ppm	< 0.0
Trace Impurities -Cobalt (Co)	<= 0.05 ppm	< 0.01
Trace Impurities -Copper (Cu)	<= 0.05 ppm	< 0.01
Trace Impurities -Gold (Au)	<= 0.3 ppm	< 0.0
Heavy Metals (as Pb)	<= 5 ppm	<3
Frace Impurities −Iron (Fe)	<= 2 ppm	< 0
Frace Impurities -Lead (Pb)	<= 0.3 ppm	< 0.0
Frace Impurities –Lithium (Li)	<= 0.1 ppm	< 0.0
Frace Impurities – Magnesium (Mg)	<= 0.2 ppm	< 0.0
Frace Impurities -Manganese (Mn)	<= 0.1 ppm	< 0.0
Trace Impurities -Nickel (Ni)	<= 0.2 ppm	< 0.0

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S pecification	Result
<= 1.5 ppm	0.0
<= 2.5 ppm	< 0.0
<= 0.1 ppm	< 0.0
<= 0.3 ppm	< 0.0
<= 2 ppm	< 0
<= 10 par/ml	3
	<= 1.5 ppm <= 2.5 ppm <= 0.1 ppm <= 0.3 ppm <= 2 ppm

For Microelectronic Use

Storage Conditions:

Country of Origin: US

Packaging Site: Paris Mfg Ctr & DC



Phillipsburg, NJ 9001.2008, 14001.2004 Paris, KY 9001.2008 Mexico city, Mexico 9001.2008 Deventer, The Netherlands 9001.2008, 14001.2004 Selangor, Malaysia 9001.2008 Panoli, India 9001.2008 Gliwice, Poland 9001.2008,17025.2005

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